

ELE 8084 Assignment 1

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Individual Parameters //

substrate: (100)

Dry Time: 100 mins

Dry Temp: 1050 °C

Wet Time: 25 mins

Wet Temp: 900 °C

a) Thickness After Dry Oxidation Step.

→ Derive the linear rate constant. (B/A)

$$B/A = D_0 \exp\left(\frac{-E_A}{RT}\right)$$

For our substrate, $D_0 = 3.7 \times 10^6$ and $E_A = 2.00 \text{ eV}$

and $T = 1323 \text{ K}$

$$B/A = 3.7 \times 10^6 \exp\left(\frac{-2.00}{8.62 \times 10^{-5} \times 1323}\right)$$

$$B/A = 0.09 \text{ nm/hr}$$

→ Now we calculate the parabolic rate constant B :

$$B = D_0 \exp\left(\frac{-E_A}{kT}\right)$$

where $D_0 = 772 \text{ Nm}^2/\text{hr}$ and $E_A = 1.23 \text{ eV}$

$$B = 772 \exp\left(\frac{-1.23}{8.85 \times 10^{-5} \times 1323}\right)$$

$$B = 0.02 \text{ Nm}^2/\text{hr}$$

→ Now, we calculate τ using $X_i = 0.025 \text{ Nm}$

$$\tau = \frac{1}{B}(X_i^2 + AX_i)$$

where $A = 0.22$

$$\tau = \frac{1}{0.02}(0.025^2 + (0.22 \times 0.025))$$

$$\tau = 0.31 \text{ hr} \quad / \quad t + \tau = 1.98 \text{ hrs}$$

→ Now, we calculate oxide thickness x_0

$$x_0 = \frac{A}{2} \left[\left(1 + \left(\frac{4B}{A^2} \right) (t + \tau) \right)^{\frac{1}{2}} - 1 \right]$$

$$X_0 = 0.11 \left[(4.28)^{\frac{1}{2}} - 1 \right]$$

$$X_0 = 0.12 \text{ nm} = 120 \text{ nm}$$

Answer to
Part (a)

(b) → Moving to wet oxidation step:

→ Follow same overall process.

→ Linear Rate constant β

$$\beta/A = D_0 \exp\left(-\frac{E_A}{kT}\right)$$

where $D_0 = 9.7 \times 10^7$, $E_A = 2.05$ and $T = 1123 \text{ K}$

$$\beta/A = 0.26 \text{ nm/hr}$$

→ Now get parabolic Rate constant:

$$\beta = D_0 \exp\left(-\frac{E_A}{kT}\right)$$

where $D_0 = 386$ and $E_A = 0.78$

$$\beta = 0.21 \text{ nm}^2/\text{hr}$$

Thus $A = 0.81$

→ Now we calculate the oxide thickness

In Areas that are etched - I.e $X_i = 0, T = 0$

$$\beta/A = 0.26, \beta = 0.21, A = 0.81, t = 0.42$$

$$X_0 = \frac{0.81}{2} \left[\left(1 + \frac{4(0.21)}{(0.81^2)} (0.42) \right)^{\frac{1}{2}} - 1 \right]$$

$$X_0 = 0.097 \text{ nm} = 97 \text{ nm}$$

→ Now we find the thickness in regions that have not been etched?

X_i is our depth after dry oxidation (0.21 nm)

→ find T ($\beta = 26 \text{ nm}/\text{hr}$)

$$T = \frac{1}{0.21} (0.12^2 + (0.81 \times 0.12))$$

$$T = 0.53 \text{ hrs} \rightarrow t + T = 0.95 \text{ hrs}$$

and so, X_0 can be found

$$X_0 = \frac{0.81}{2} \left[\left(1 + \frac{4(0.21)}{(0.81^2)} (0.95) \right)^{\frac{1}{2}} - 1 \right]$$

$$X_0 = 0.198 \text{ nm} = 198 \text{ nm}$$

O To Summarise :

- After the initial dry oxidation, the oxide thickness is 120nm

O After wet oxidation, and in regions

that are etched, the oxide thickness is

97nm

O After wet oxidation, and in regions

that are not etched, the oxide thickness

is 198nm

O Step height is reduced to ~~to~~ 101nm

(2)

→ We need to iterate through each element

Element 1

$$\frac{1}{R_E} = \frac{1}{559} - \frac{1}{953} \rightarrow R_E = 1352\Omega$$

→ Now, we calculate the resistivity ρ_e :

$$\rho_e = R_E \times t = 1352 \times 200 \times 10^{-7} \Omega$$

$$\rho_e = 0.027\Omega\text{-cm}$$

→ We can make a first guess at N_n as

we know the initial concentration of $1 \times 10^{16} \text{ cm}^{-3}$

→ On the graph, a total dopant concentration of 10^{16} cm^{-3} equates to a $N_n = 1050$

→ Subbing into our equation:

$$N = \frac{1}{q N_n \rho_e} = \frac{1}{1.6 \times 10^{-19} \times 1050 \times 0.027}$$

$$N = 2.2 \times 10^{17} \text{ cm}^{-3}$$

→ From the graph, this is not valid and so we need to iterate again.

→ If we go to $n = 2.2 \times 10^{17} \text{ cm}^{-3}$ on graph and

read Extrapolate to N_n , we get $N_n = 500$

→ Repeating calculation of

$$N = \frac{1.6 \times 10^{-19} \times 500 \times 0.02}{1}$$

$$N = 4.63 \times 10^{17} \text{ cm}^{-3}$$

→ This still isn't valid, so we repeat.

We go $N_n = 400$

$$N = 5.79 \times 10^{17} \text{ cm}^{-3}$$

We go $N_n = 350$

$$N = 6.61 \times 10^{17} \text{ cm}^{-3}$$

At $N_n = 350$, $n = 6.61 \times 10^{17} \text{ cm}^{-3}$ the results

have converged -

The first element concentration (Depth = 100nm)

$$= 6.61 \times 10^{17} \text{ cm}^{-3}$$

2nd Element

$$\frac{1}{R_E} = \frac{1}{953} - \frac{1}{2169} \rightarrow R_E = 1700 \Omega$$

\rightarrow Resistivity ρ_e

$$\rho_e = 1700 \times 200 \times 10^{-3} = 0.034 \Omega \text{cm}$$

Iterate, start at $N_n = 350$

$$n = 5.25 \times 10^{17} \text{ cm}^{-3} \Rightarrow \text{Not valid}$$

$$N_n = 400 \Omega$$

$$n = 4.08 \times 10^{17} \text{ cm}^{-3} \Rightarrow \text{Not valid}$$

$$N_n = 450 \Omega$$

$$n = 4.08 \times 10^{17} \text{ cm}^{-3} \Rightarrow \text{Valid}$$

88

2nd layer concentration (Depth = 300 nm)

$$n = 4.08 \times 10^{17} \text{ cm}^{-3}$$

Element 3

$$\frac{1}{R_E} = \frac{1}{2169} - \frac{1}{7505} \rightarrow R_E = 3051 \Omega/\square$$

→ Resistivity ρ_e

$$\rho_e = 3051 \times 200 \times 10^3 = 0.061 \Omega \text{cm}$$

Iterating, start with $N_n = 450$

$$n = 2.28 \times 10^7 \Rightarrow \text{Not valid.}$$

$$N_n = 500 \text{ :}$$

$$n = 2.05 \times 10^7 \text{ cm}^{-3} \Rightarrow \text{Not valid}$$

$$N_n = 600 \text{ :}$$

$$n = 1.71 \times 10^7 \text{ cm}^{-3} \Rightarrow \text{Not valid}$$

$$N_n = 650 \text{ :}$$

$$n = 1.58 \times 10^7 \text{ cm}^{-3} \Rightarrow \text{Valid}$$

3rd layer, thickness (500nm)

$$n = 1.58 \times 10^7 \text{ cm}^{-3}$$

Element 4

$$\frac{1}{R_E} = \frac{1}{7505} - \frac{1}{54650} \Rightarrow R_E = 8700 \Omega/\alpha$$

→ Resistivity ρ_e

$$\rho_e = 8700 \times 200 \times 10^{-3} = 0.174 \Omega \text{cm}$$

Iterating, start at $N_n = 600$

$$n = 5.99 \times 10^{16} \text{ cm}^{-3} \Rightarrow \text{Not Valid}$$

$$N_n = 700$$

$$n = 5.13 \times 10^{16} \text{ cm}^{-3} \Rightarrow \text{Not Valid}$$

$$N_n = 800$$

$$n = 4.49 \times 10^{16} \text{ cm}^{-3} \Rightarrow \text{Not Valid}$$

$$N_n = 900$$

$$n = 3.99 \times 10^{16} \rightarrow \text{Valid}$$

$$4^{\text{th}} \text{ element conc. (200nm)} = 3.99 \times 10^{16} \text{ cm}^{-3}$$

- Element 5 is at the end of the diffusion layer -

Data Summary

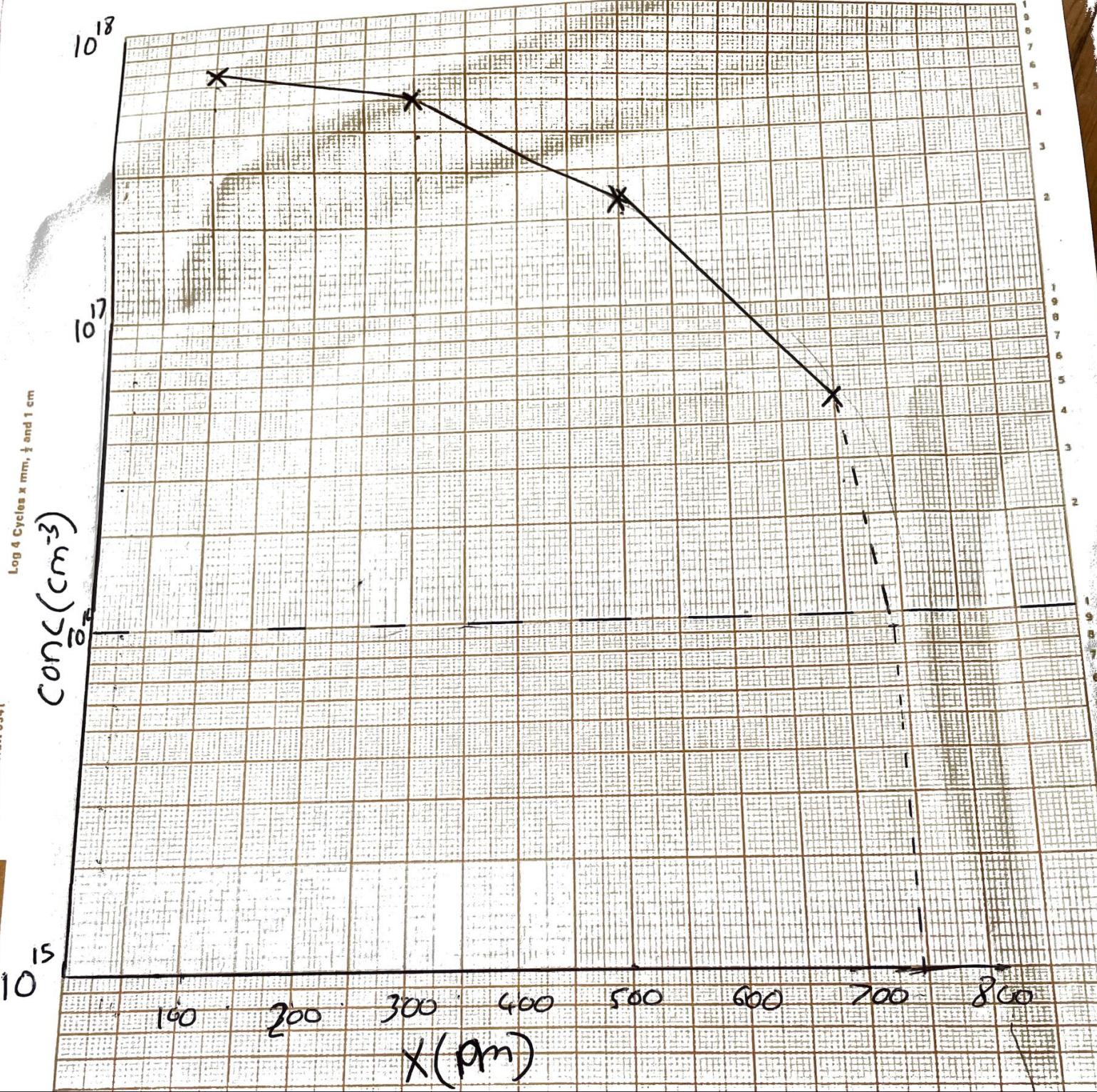
Element	Centre	Rsheet	Pc	n (cm^{-3})
1	100	1352	0.027	6.61×10^{17}
2	300	1700	0.034	4.08×10^{17}
3	500	3051	0.061	1.58×10^{17}
4	700	8700	0.174	3.99×10^{16}

→ Plot on graph paper

The junction Depth is the depth where the Dopant concentration is equal to the background dopant

$(1 \times 10^{16} \text{ cm}^{-3})$

→ We can Estimate the junction Depth to be $\sim 750 \text{ nm}$



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Individual Parameters:

Oxide: 80 nm, Dose: $6 \times 10^{12} \text{ cm}^{-2}$

Energy: 120 keV, Time: 50 mins, Temp: 1000°C

a) Junction Depth immediately after implantation.

○ Get Relevant Straggle and Range Data from Table.

○ At our Energy (120 keV), $R_p = 148 \text{ nm}$

and $\Delta R_p = 40 \text{ nm}$

○ The junction Depth is the Depth at which our implantation concentration equals the background concentration (2×10^{15})

→ Now, we can solve the Question

⇒

$$R_p = 148 \text{ nm} = 0.148 \mu\text{m}$$

$$\Delta R_p = 40 \text{ nm} = 0.04 \mu\text{m}$$

→ We can approximate the implanted profile as

$$C(x) = C_p \exp\left(\frac{-(\beta c - R_p)^2}{2\Delta R_p^2}\right)$$

Where : $C_p = \frac{Q_T}{\sqrt{2\pi} \Delta R_p}$

Calculating C_p from our single Data $\Delta R_p = 40 \text{ nm}$

and dose (Q_T) $\approx Q_T = 6 \times 10^{12} \text{ cm}^{-2}$, we get as

$$C_p = \frac{6 \times 10^{12} \text{ cm}^{-2}}{\sqrt{2\pi} \times 0.04}$$

$$C_p = 5.98 \times 10^{16} \text{ cm}^{-3}$$

And Now the full term $C(x)$

$$C(x) = 5.98 \times 10^{16} \exp\left(\frac{-(0.148 - 0.148)^2}{2 \times 0.04}\right)$$

$$C(x) = 5.98 \times 10^{16} \text{ cm}^{-3}$$

→ The Junction Depth, with a background doping concentration $2 \times 10^{15} \text{ cm}^{-3}$

We can get the junction Depth by

$$x_j = R_p \pm DR_p \sqrt{2 \ln \frac{C_p}{C_B}}$$

$$x_j = 0.148 \pm 0.04 \sqrt{2 \ln \frac{5.98 \times 10^{16}}{2 \times 10^{15}}}$$

$$x_j = 0.148 \pm 2.6 \text{ nm}$$

Two Junctions are formed, but only one is valid

$$x_j = 0.148 + 2.6$$

$$x_j = 2.748 \text{ nm}$$

b) Junction Depth after Drive in:

$$D_0 = 10.5 \text{ cm}^2/\text{s}$$

$$E_A = 3.6 \text{ eV}$$

→ We start by calculating the Diffusion coefficients for phosphorus:

$$D = D_0 e^{-\frac{E_A}{kT}}$$

$$D = 10.5 \exp\left(\frac{-3.69}{8.83 \times 10^{-6} \times 1273}\right)$$

$$D = 2.61 \times 10^{-14} \text{ cm}^2/\text{s}$$

Multiplying by the Drive in Time:

$$Dt = 2.61 \times 10^{-14} \times 3000$$

$$Dt = 7.83 \times 10^{-11} \text{ cm}^2$$

Now we can Equate the concentration Equations:

$$C_B = \frac{QT}{\sqrt{2\pi(4R_p^2 + 2DE)}} \exp\left(\frac{-(x - R_p)^2}{2DR_p^2 + 4DE}\right)$$

$$2 \times 10^{15} = \frac{6 \times 10^{12}}{\sqrt{2\pi(4 \times 10^{-12})^2 + 2(7.83 \times 10^{-11})}} \exp\left(\frac{(x - 10^{-12})^2}{2(7.83 \times 10^{-11})}\right)$$

$$2 \times 10^{15} = 3.74 \times 10^{17} \exp\left(-\frac{(x - 0.000148)^2}{2((4 \times 10^{-6}) + 2(7.83 \times 10^{-11}))}\right)$$

Now, we need to solve this for x .

$$\frac{2 \times 10^{15}}{3.74 \times 10^{17}} = \exp\left(-\frac{(x - 0.000148)^2}{2((4 \times 10^{-6}) + 2(7.83 \times 10^{-11}))}\right)$$

$$\ln(0.0053) = -\frac{(x - 0.000148)^2}{8 \times 10^{-6}}$$

$$-4.2 \times 10^{-5} = -(x - 0.000148)(x - 0.000148)$$

$$-4.2 \times 10^{-5} = -(x^2 - 0.000148x - 0.000148x + 2.19 \times 10^{-8})$$

$$-4.2 \times 10^{-5} = -x^2 + 2.19 \times 10^{-8}$$

$$x = 0.0065 \text{ m} = 6.5 \text{ mm}$$